(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization

International Bureau



(43) International Publication Date 19 February 2004 (19.02.2004)

PCT

(10) International Publication Number WO 2004/014879 A1

- (51) International Patent Classification⁷: C07D 261/08, C07K 7/56
- (21) International Application Number:

PCT/JP2003/009900

- (22) International Filing Date: 4 August 2003 (04.08.2003)
- (25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data: 2002-231182

8 August 2002 (08.08.2002)

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- (81) Designated States (national): JP, US.
- (84) Designated States (regional): European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR).

Published:

with international search report

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: NEW PROCESS

$$R^{\frac{1}{2}}A^{\frac{1}{2}}$$
 $N=0$ $A^{\frac{2}{2}}R^{\frac{2}{2}}$

(57) Abstract: The present invention relates to a process for preparing a pharmaceutical starting compound compound by hydrolyzing a compound of the general formula (II): Wherein R¹ is protected carboxy, R² is lower alkoxy or higher alkoxy, A¹ is an aromatic bivalent group, hererocyclic bivalent group or cyclo (lower) alkane bivalent group, and A² is an aromatic bivalent group, heterocyclic bivalent group or cyclo (lower) alkane bivalent group, with aqueous potassium hydroxide and by treating with hydrochloric acid.